

Modules of the 2025 course

Topics covered	No	Lecture/Date
VAT Photo polymerization (history) – DLP printer – light engine – part I	5	20.03.2025
DLP printer – chemical components in a photoresin – role of oxygen – CLIP method– part II	6	27.03.2025
Tomographic Volumetric Additive Manufacturing (TVAM): principles and applications	7	03.04.2025
Two photon Polymerization : nanoscale printing	8	10.04.2025
Two photon Polymerization : applications	9	17.04.2025
EASTER BREAK		22.04.2025
Prof. Paul Dalton, University of Oregon: Met Electro Writing (nanoscale)	10	1.05.2025
Gari Arutinov, Holst Center for AM: Mass transfer of microcomponents	11	08.05.2025
Julian Schneider: Scrona	12	15.05.2025
Patrizia Richner: Sonova (hearing aids). // Design Competition	13	22.05.2025

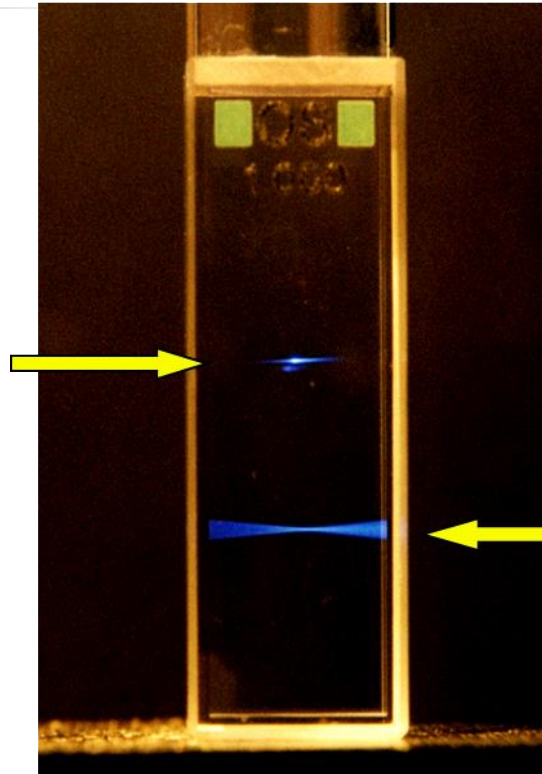
QUIZZ #2

2 Photon printing



Recap: Two-photon absorption

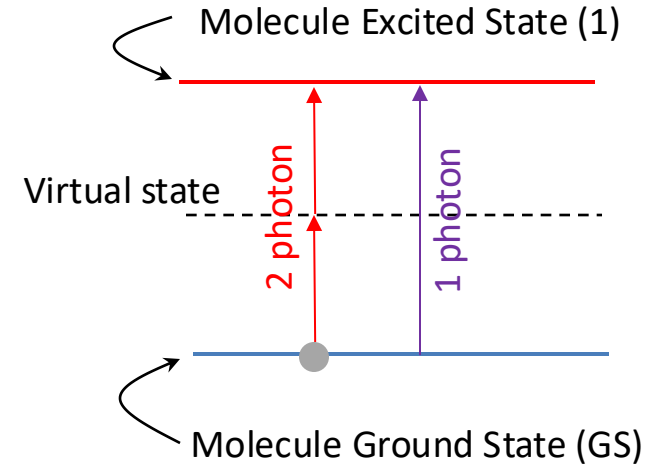
Excitation by two photons is confined to a volume very close to focus where intensity is highest, giving rise to *pinpoint 3D resolution*



Excitation by one photon results in absorption along the entire path of the laser beam in the cuvette.

Two-photon absorption

Example: 2 photons infrared of wavelength $\lambda_1 = 800 \text{ nm}$ () have a combined energy of () and can produce absorption at ()



In terms of absorption for the light intensity

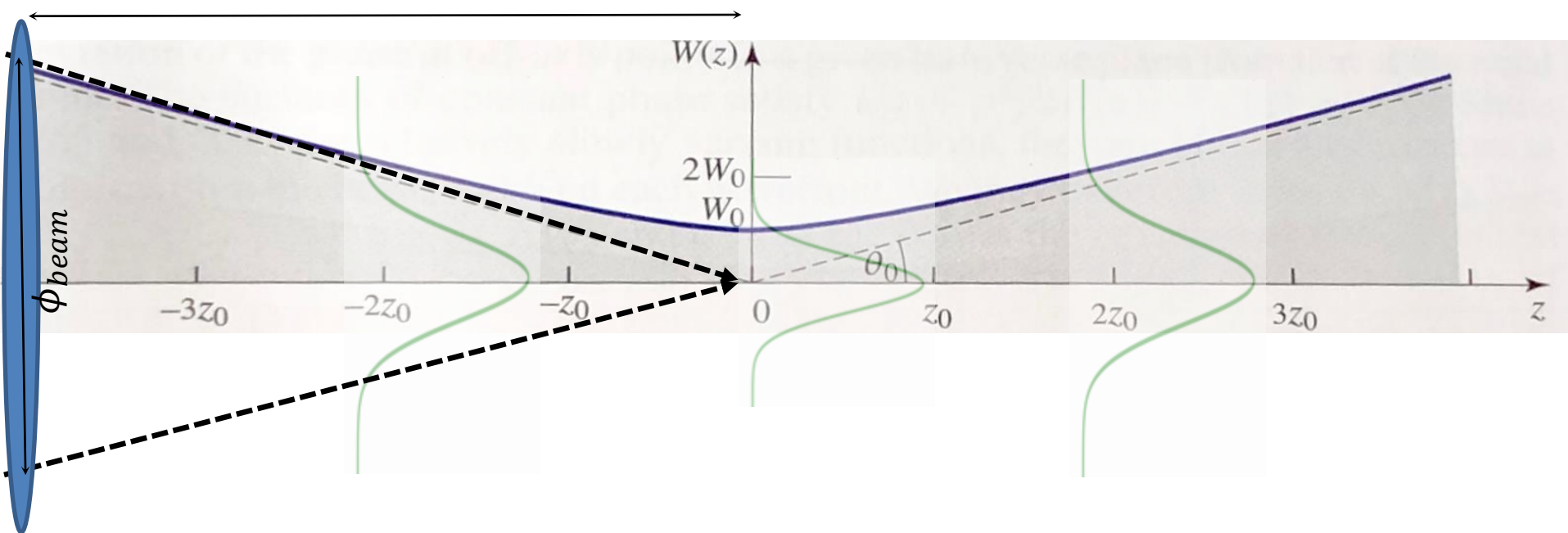
Single photon

Two photon

Estimation of the light intensity required to have a two-photon absorption of similar magnitude to single photon absorption:

Typ. Values

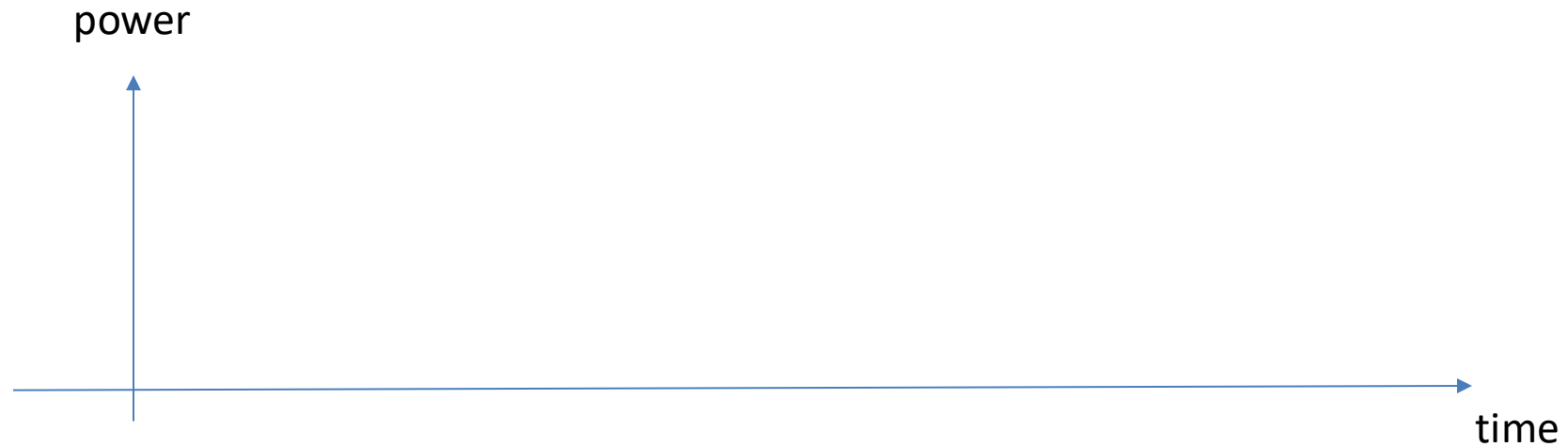
Recap: Two-photon absorption



Two-photon absorption

How to generate a laser power of 860 kW ?

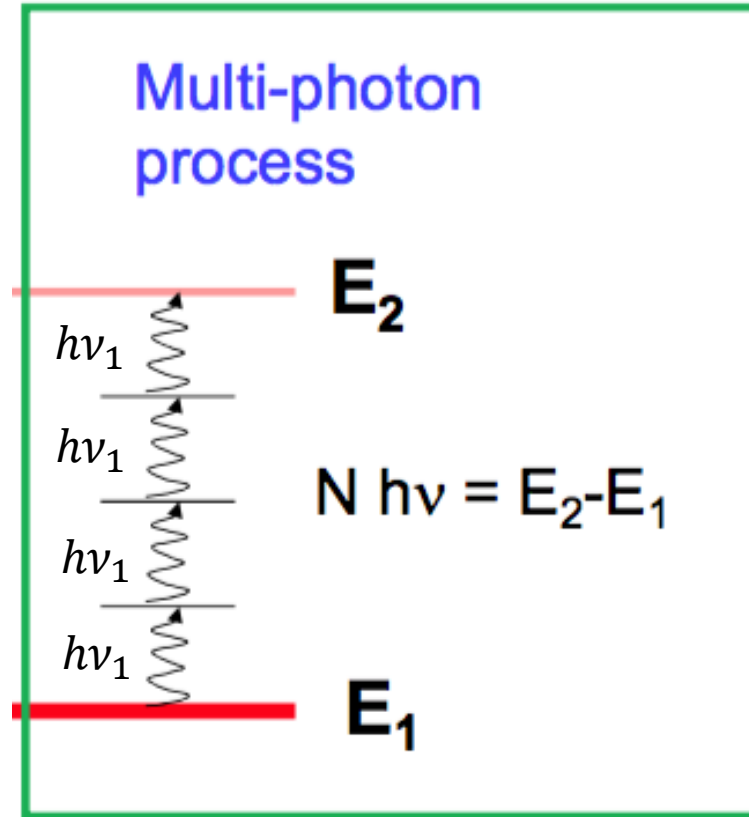
Ans: pulsed laser



Multi-photon absorption

A material is transparent at a wavelength of λ_1 (i.e frequency) but can become absorptive at very high optical peak powers

When $N=2$, the process is called Two photon absorption (TPA)

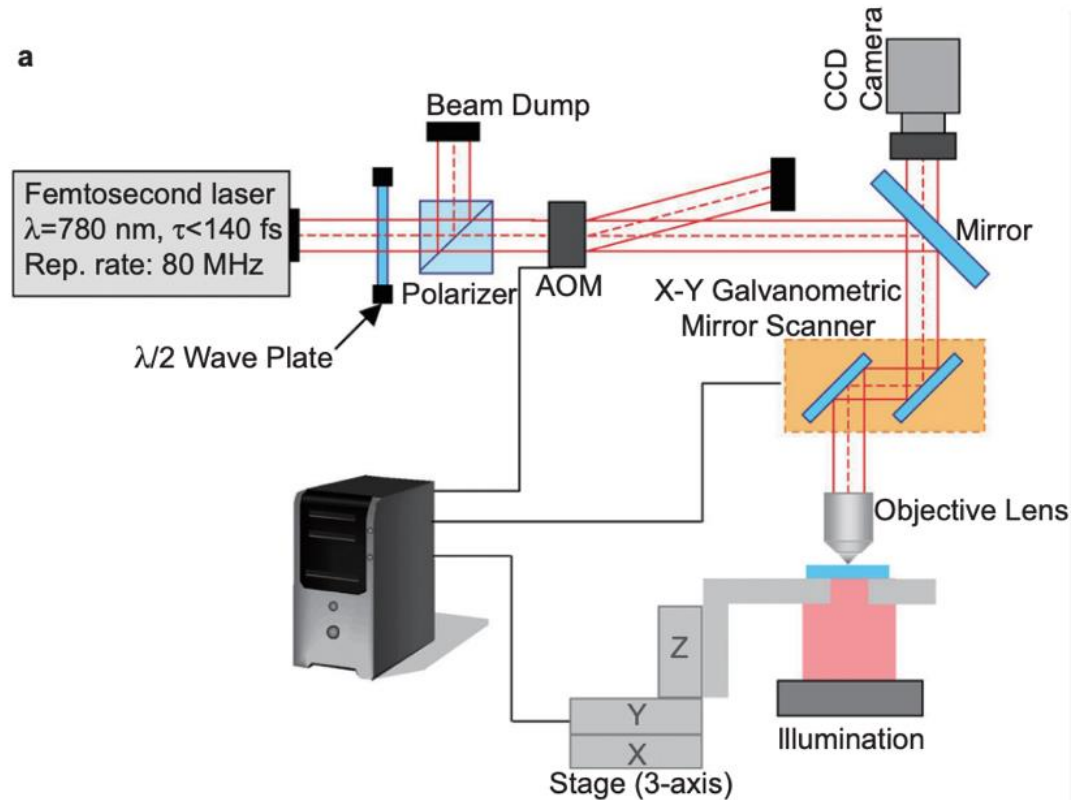


Two-photon absorption

		τ	$P_{average}$	$1/T$	
FemtoFiber smart 780	$785 \pm 5 \text{ nm}$	$< 100 \text{ fs (typ. 80 fs)}$	$> 120 \text{ mW (typ. 140 mW)}$	80 MHz	16



Typical setup for 2-photon polymerization

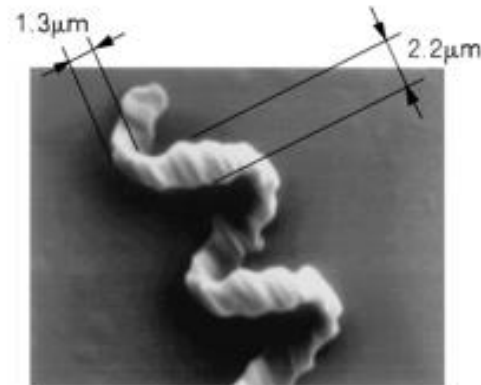
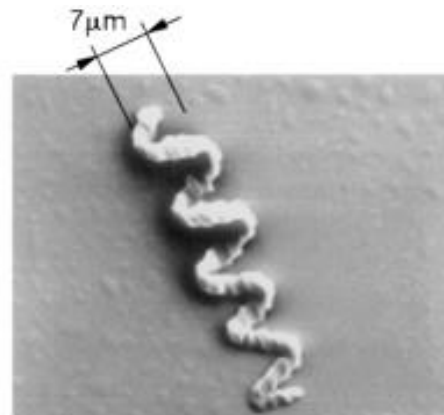


Three-dimensional microfabrication with two-photon-absorbed photopolymerization

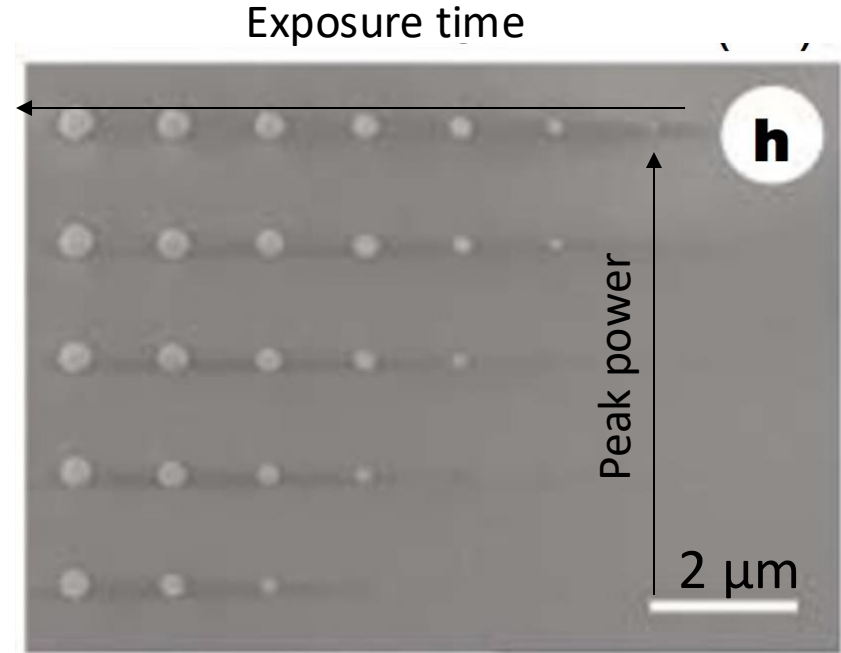
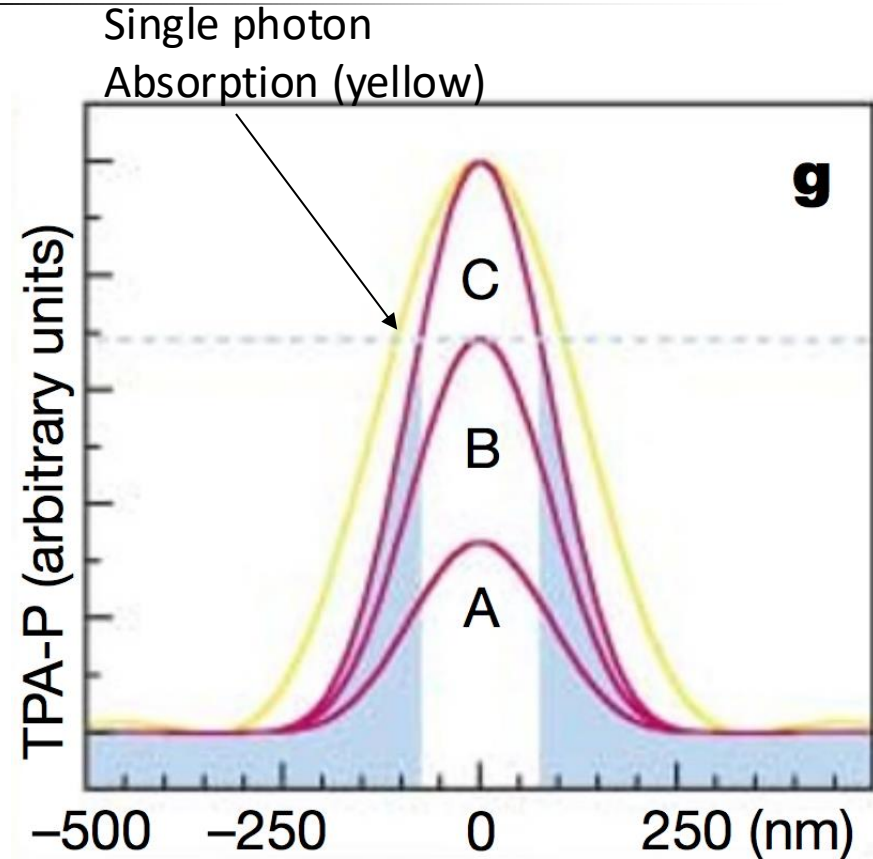
Shoji Maruo, Osamu Nakamura, and Satoshi Kawata

Department of Applied Physics, Osaka University, Suita, Osaka 565, Japan

For microfabrication of three-dimensional structures from the proposed method. The light source that we used for the two-photon absorption was a mode-locked Ti:sapphire laser whose oscillating wavelength, pulse width, repetition rate, and peak power were 790 nm, 200 fs, 76 MHz and 50 kW, respectively. The Ti:sapphire laser was excited by an Ar-ion laser of 8-W average power. The beam of the laser was focused into the resin with an objective lens whose N.A. was 0.85. A stage support



Printed voxel size



Printed voxel size

Energy per pulse: $E_{pulse} = 137 \text{ pJ}$

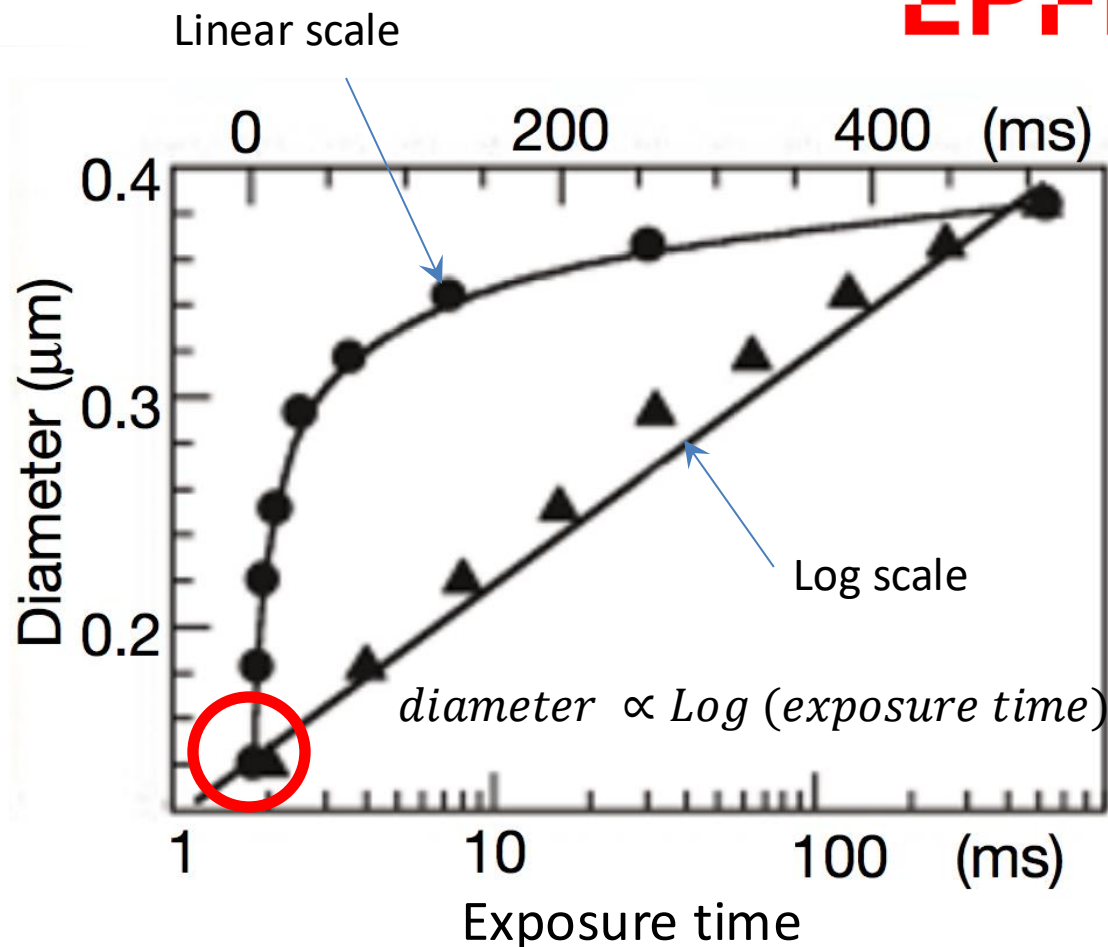
Pulse duration: $\tau = 150 \text{ fs}$

$P_{peak} =$

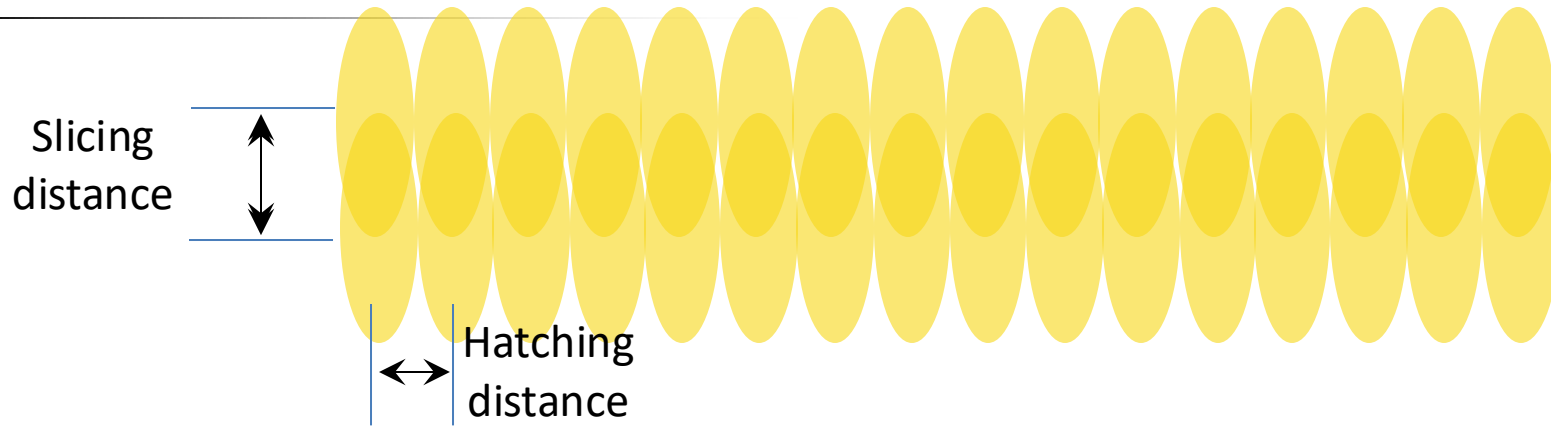
Numerical aperture $NA=1.4$

$waist =$

$I = \quad = \quad \text{GW/mm}^2$



Fabrication time depends also on the scanning step



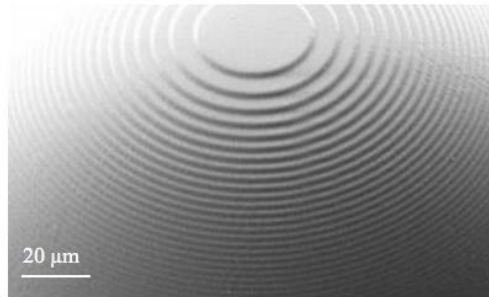
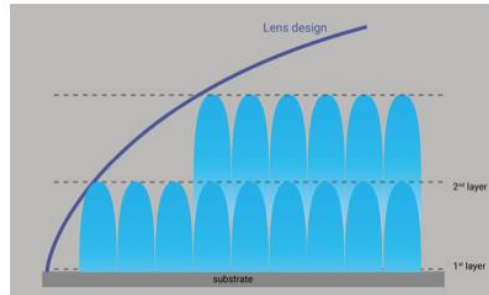
Scanning steps can be smaller to make a smooth surface



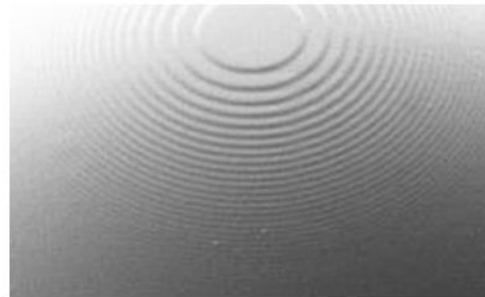
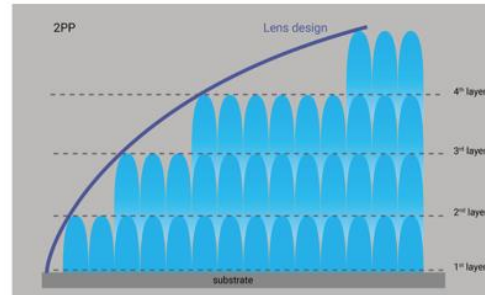


Challenge in high-precision 3D printing

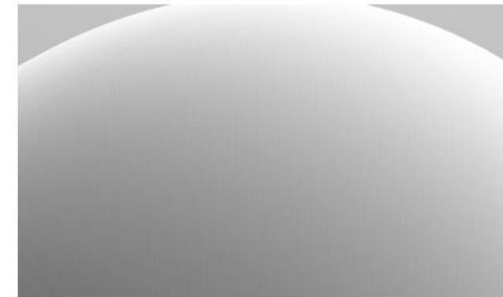
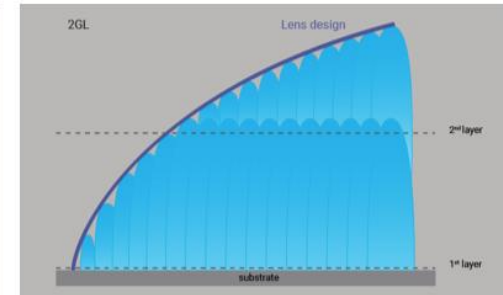
Staircasing vs. printing speed



2PP with coarse slicing



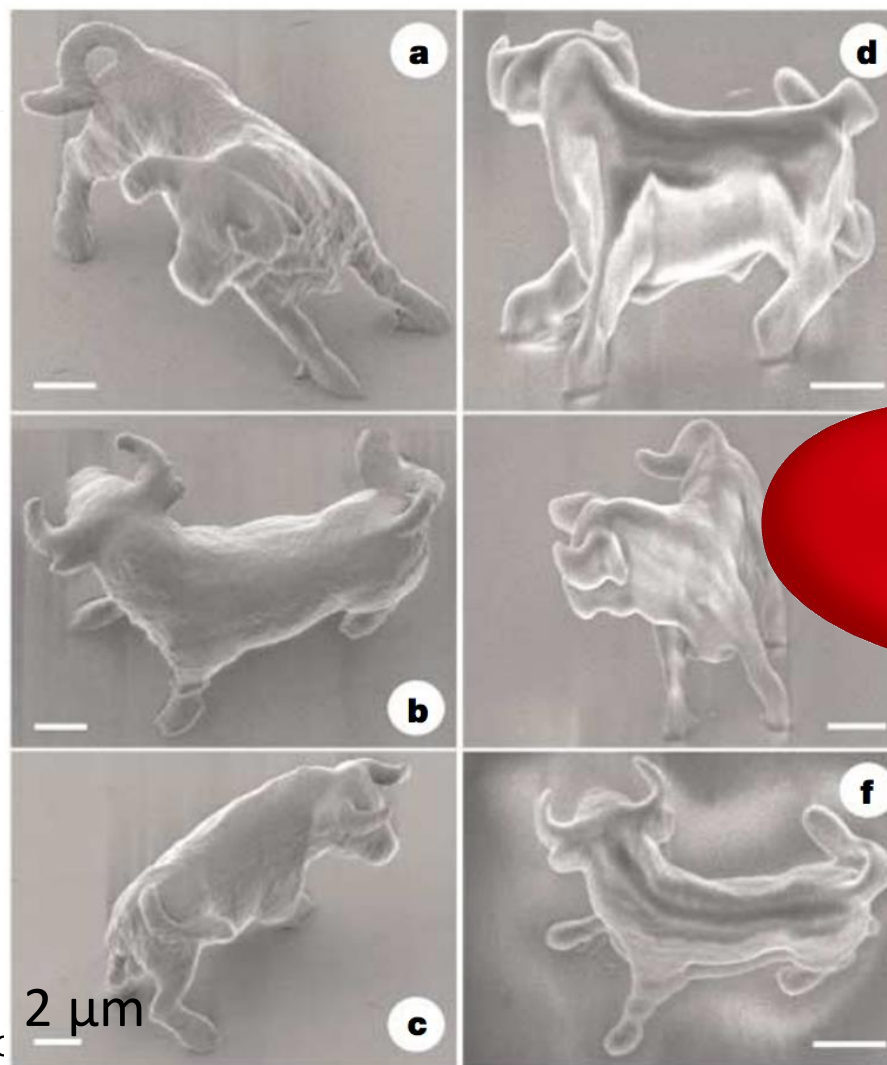
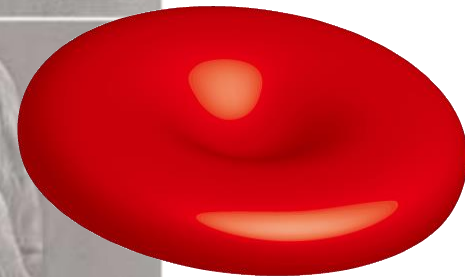
2PP with fine slicing



2GL[®] with coarse slicing

Courtesy of
NanoScribe

A red blood cell for comparison



2 μ m

Example:
20 x 20 x 20 μ m

2 ms exposure
Hatching-slicing (x,y,z): 0.15 μ m.

#points =

Exposure time =

Although the wavelength is 780nm,
It is possible to make structures
With size 65 nm !!

By adjusting the dose i.e
*Intensity * exposure times*

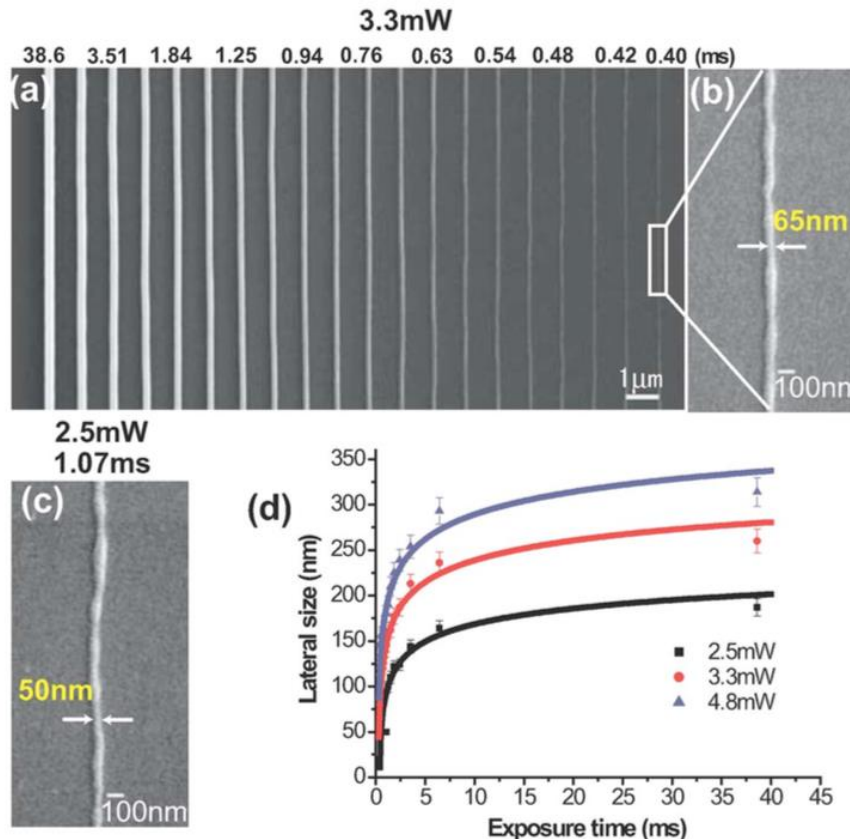
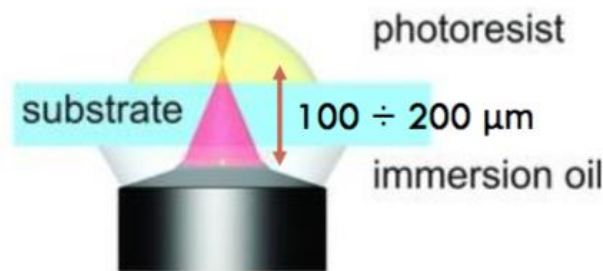
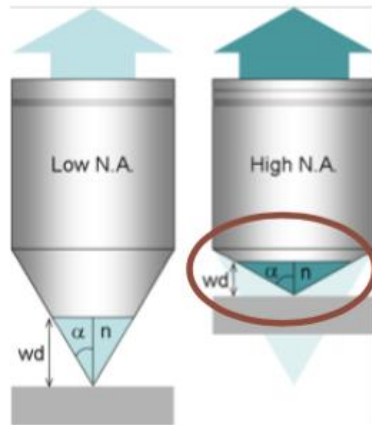


FIG. 2. (Color online) (a) SEM images of photocured polymer lines obtained using a laser power of 3.3 mW, after various exposure times. (b) Enlarged image of a line fabricated with a laser power of 3.3 mW and an exposure time of 0.4 ms. (c) A polymer line with a width of 50 nm. (d) LSR MICRO -vs exposure time under different laser powers (lines are calculated results).

Height Limitation of 3D structures



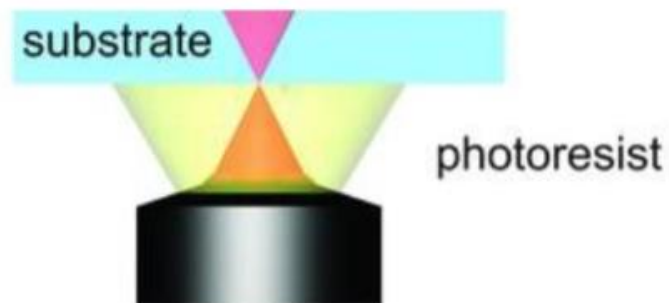
E.G.: Zeiss Objective Plan-Apochromat
63x/1.40 Oil DIC

- $M=63x$
- $NA=1.4$
- $WD=190 \mu m$

Max height $\sim 10 \mu m$

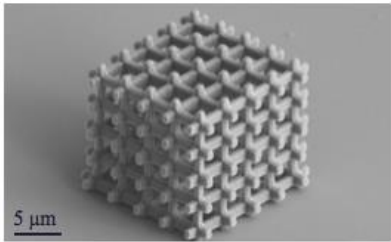
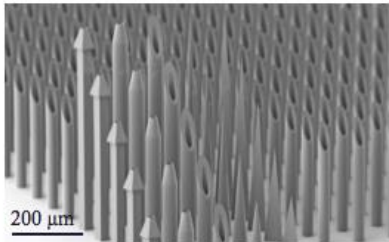

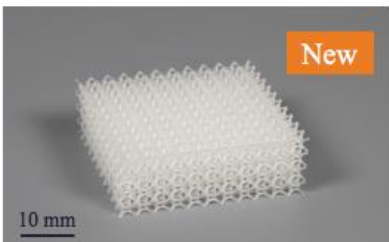
DW: Working distance of the microscope objective i.e
The distance between the objective and the focal distance

- DIP-IN



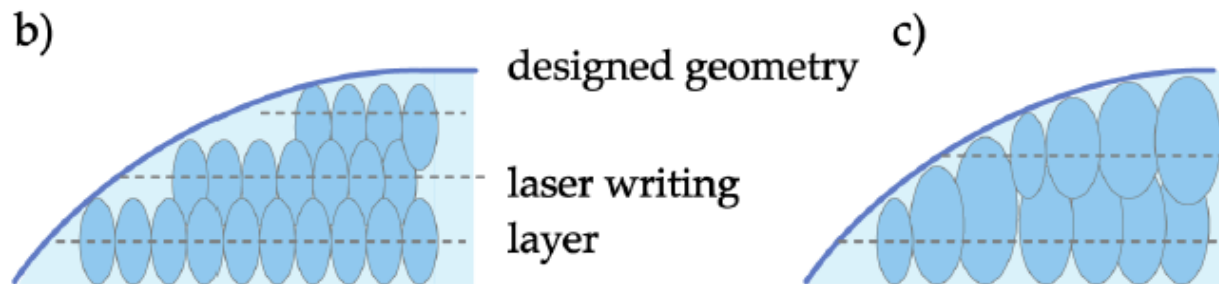
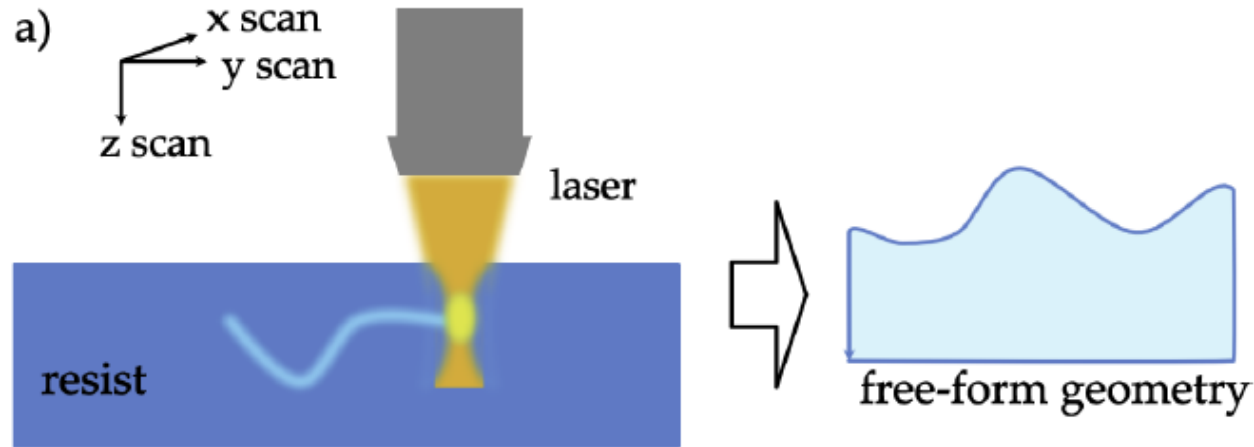
Only photoresists with matched n
can be used

Dip-in mode

	Small feature	Medium feature	Large features	Extra large feature
				
Magnification	63x	25x	10x	5x
NA	1.4	0.8	0.3	0.16
Calibrated print field diameter	270 μm	700 μm	1,750 μm	3,200 μm
Working distance	360 μm	380 μm	2,600 μm	18,500 μm
Scan speed (max.)	100 mm/s	250 mm/s	625 mm/s	1,250 mm/s
Slicing range (typical)	0.1 – 0.8 μm	0.5 – 3 μm	2 – 10 μm	5 – 100 μm

Two-photon polymerization (2PP)

Two-photon grayscale lithography (2GL)



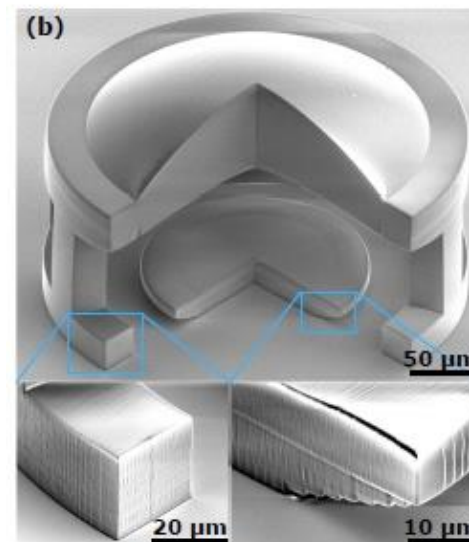
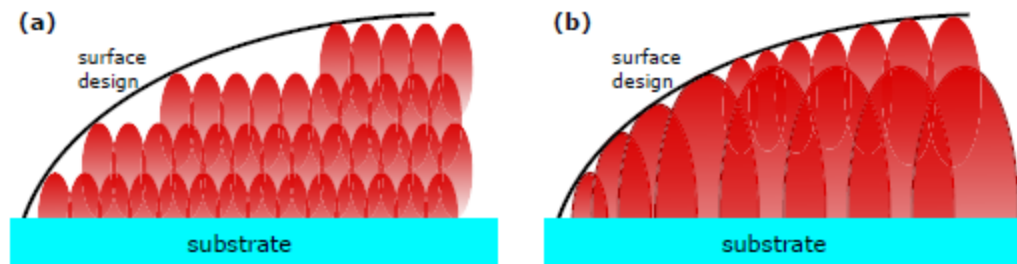


Complex aspherical singlet and doublet microoptics by grayscale 3D printing

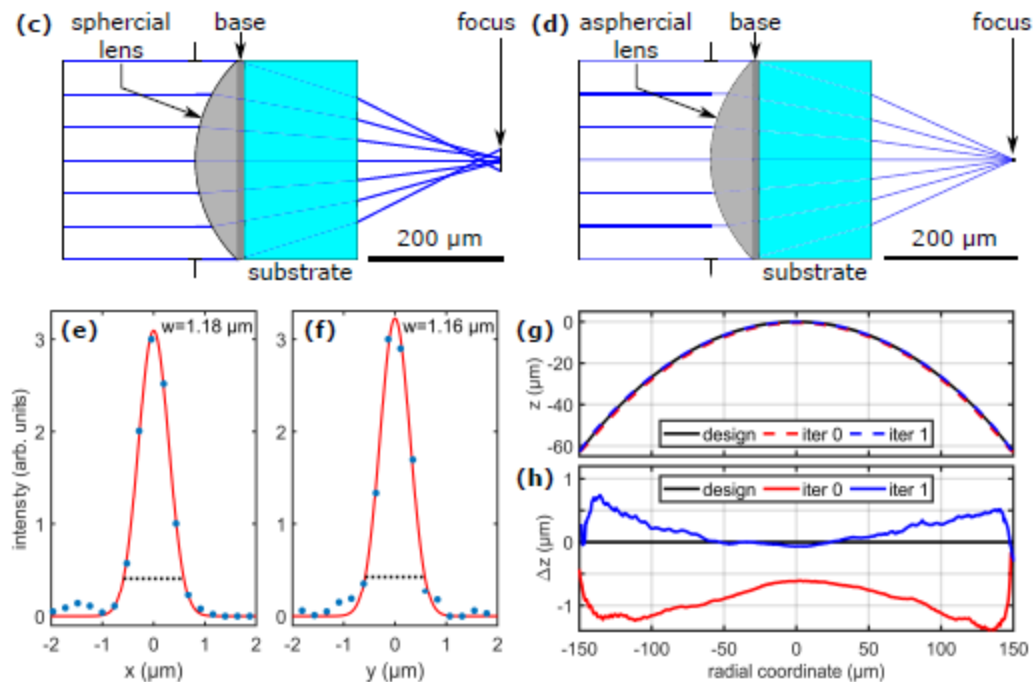
LEANDER SIEGLE,*  SIMON RISTOK,  AND HARALD GIESSEN 

4th Physics Institute and Research Center SCoPE, University of Stuttgart, Pfaffenwaldring 57, 70569 Stuttgart, Germany

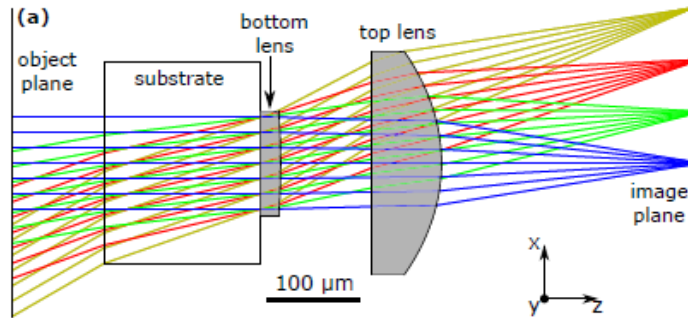
*l.siegle@pi4.uni-stuttgart.de



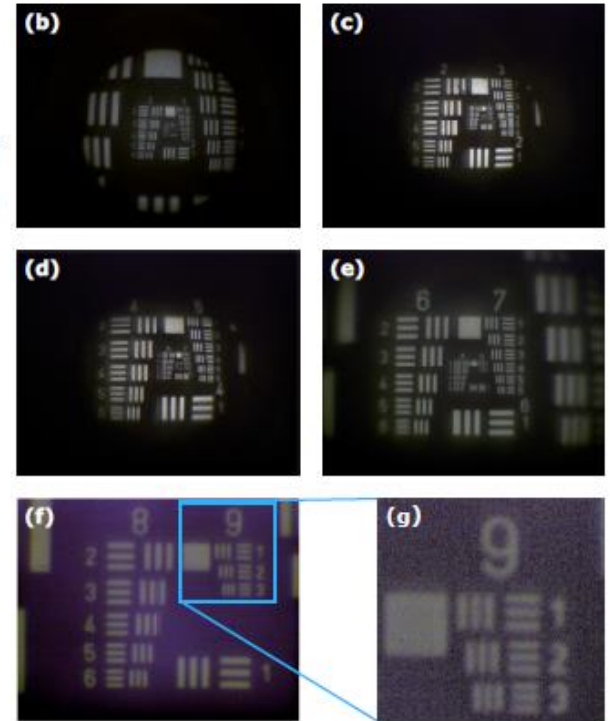
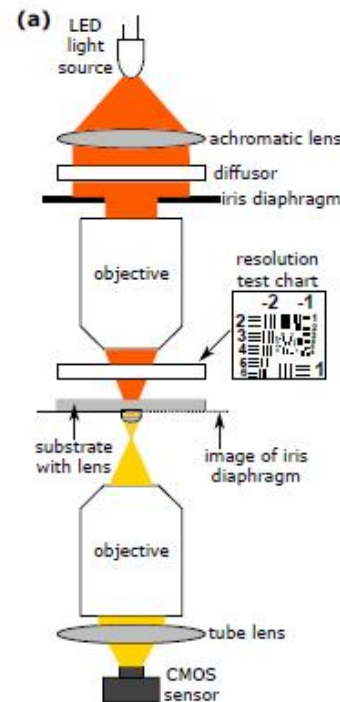
2GL on Aspherical Singlet and Doublet



2GL on Aspherical Singlet and Doublet

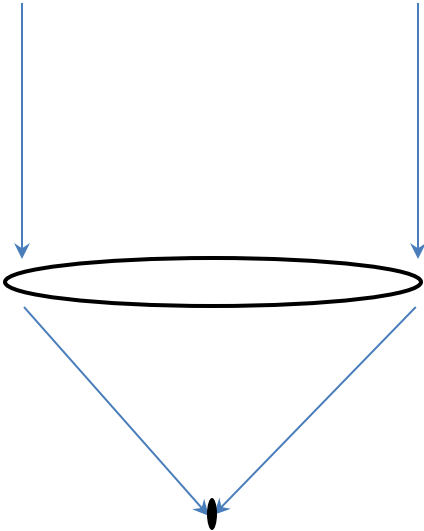


field of view of 60°
deviations 20 nm for the bottom lens
deviations 100 nm for the larger top lens
resolution 645 lp/mm

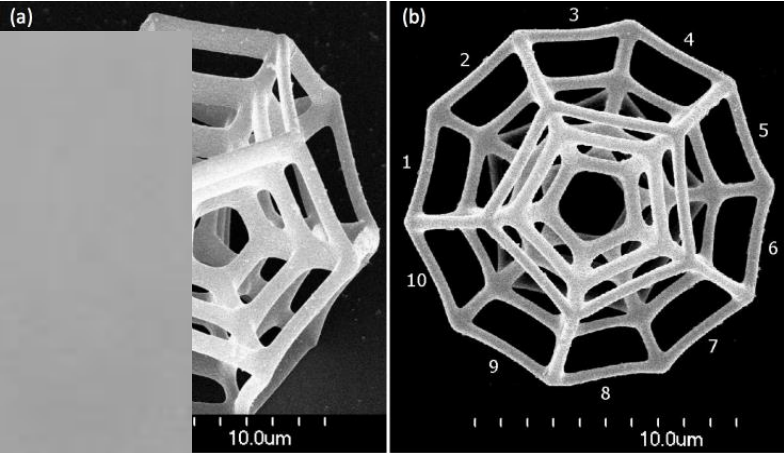
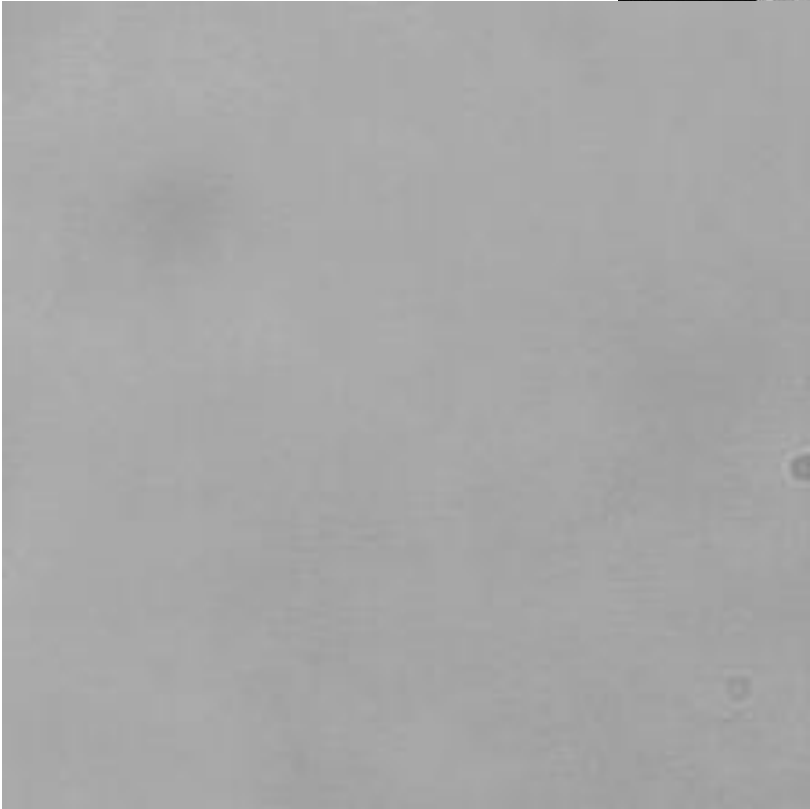


How to increase printing speed ?

Holographic multi-focus 3D two-photon polymerization with real-time calculated holograms – Optics Express 2014



Single focus



Fabricated by 550 projections giving each 5 Foci.

This can be generated by
DLP for example
and other advanced Additive manufacturing technologies

Example: bio-printing

5 ms exposure, 3 mW/foci \rightarrow 200 Hz
750 foci \rightarrow 2.2 W



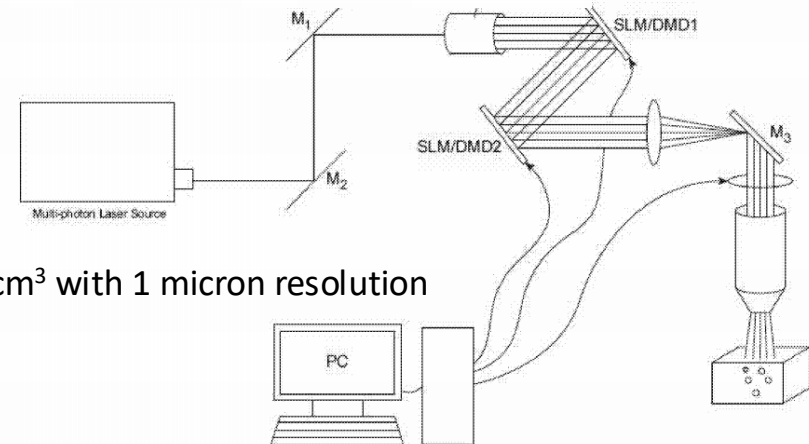
(19) **United States**
(12) **Patent Application Publication**
MATHEU

EPFL

(54) **METHODS AND SYSTEMS FOR PRINTING BIOLOGICAL MATERIAL**

(71) Applicant: **Prellis Biologics, Inc.**, San Francisco, CA (US)

(52)



Time to print 1 cm³ with 1 micron resolution

$$fab\ time = f \cdot n_{voxels} / \#voxels/sec$$

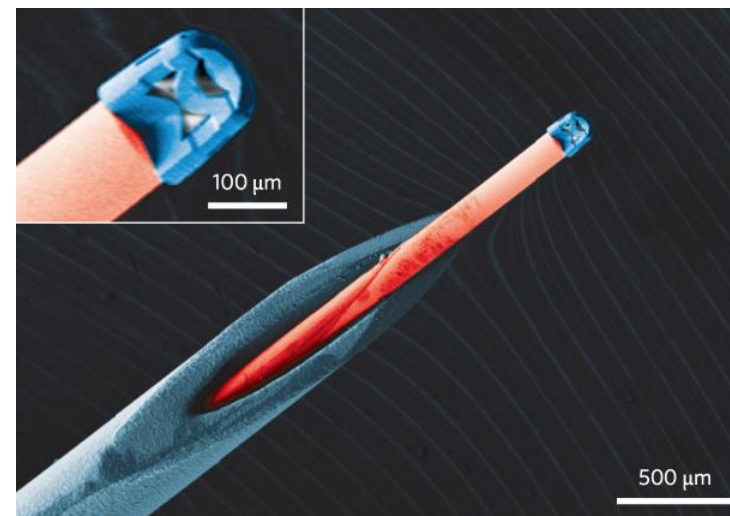
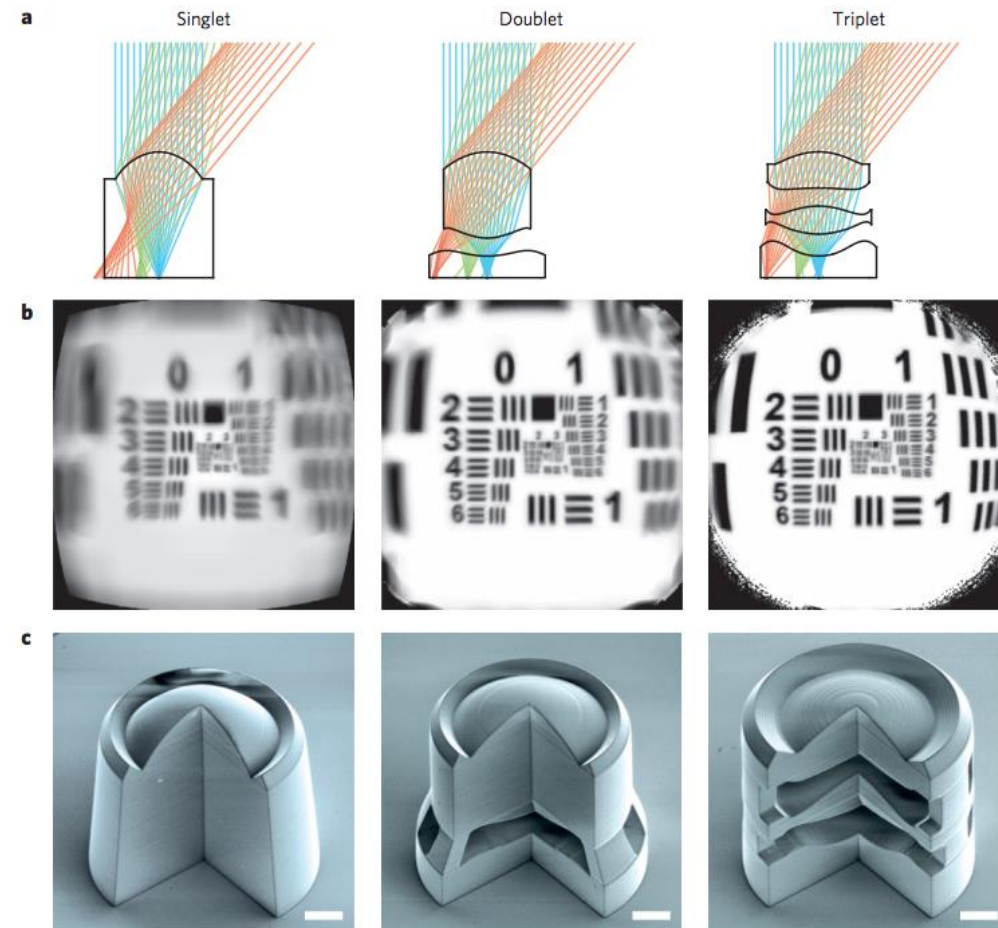
Fill factor 1%

15%

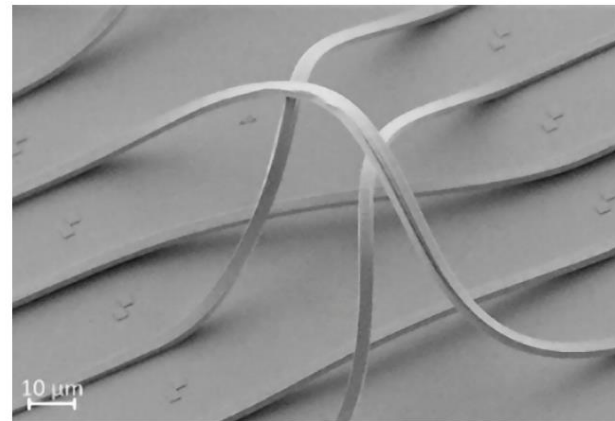
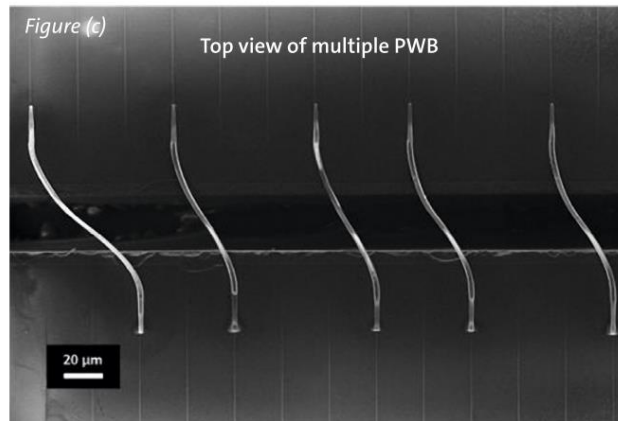
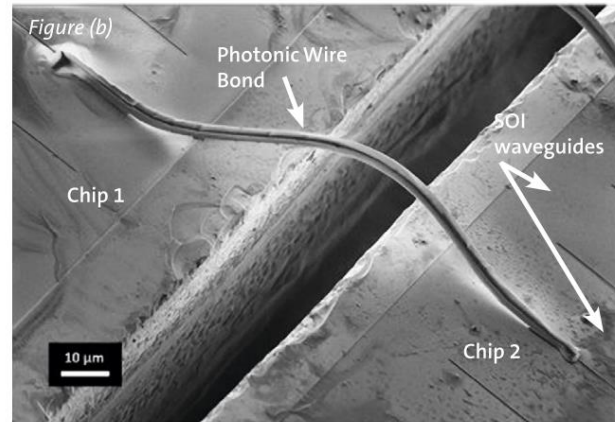
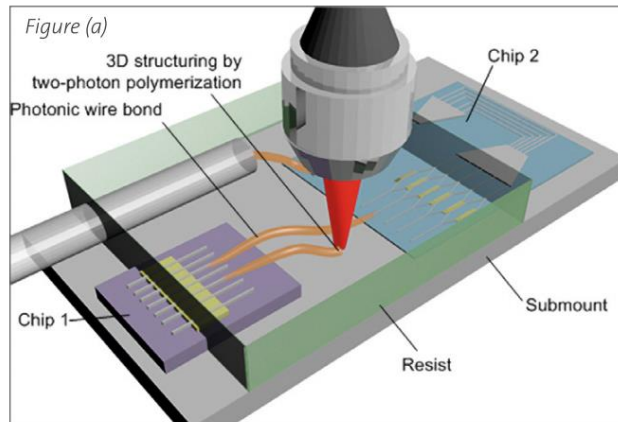
18.5 h

11.5 days

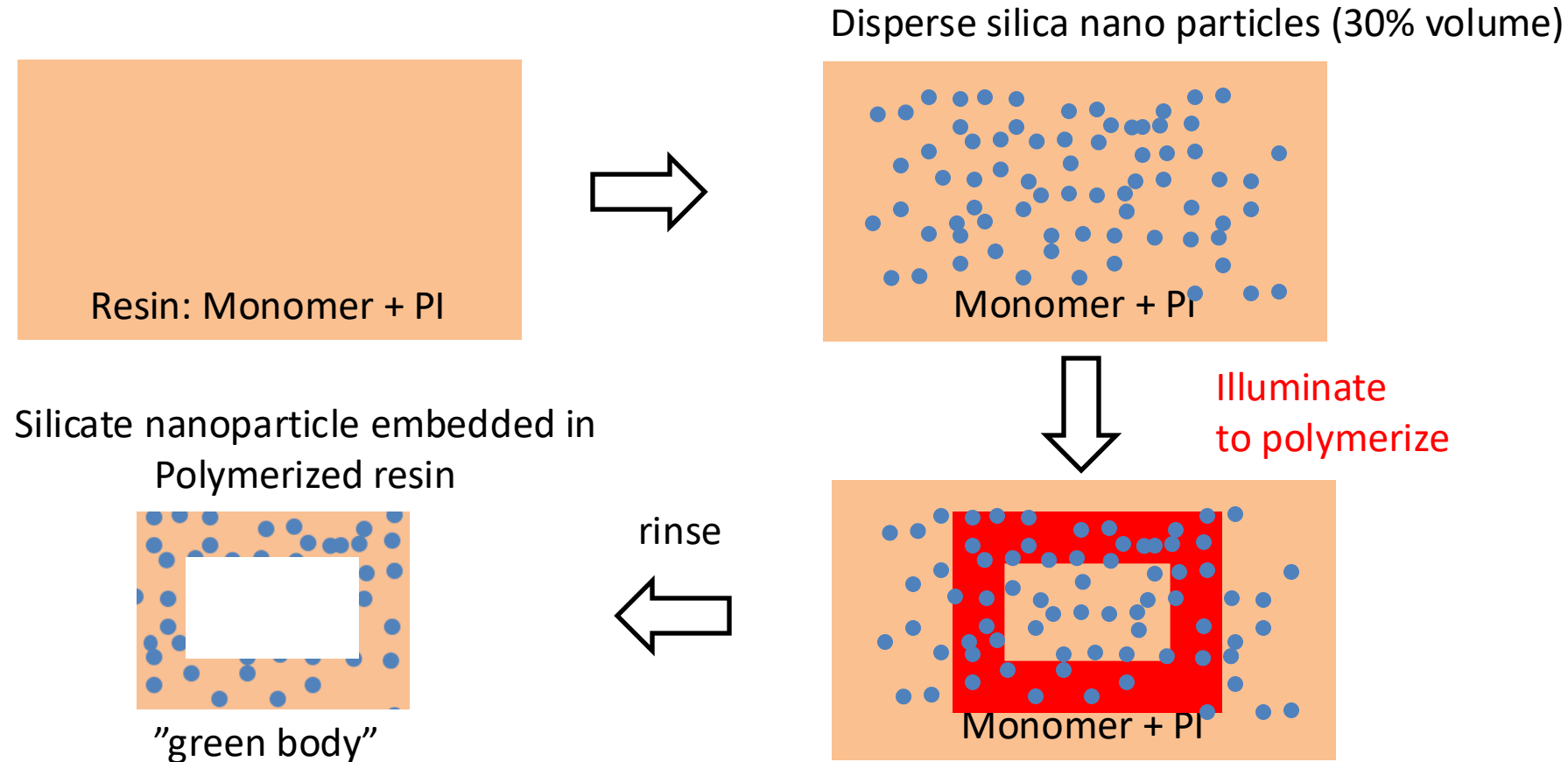
Two-photon direct laser writing of ultracompact multi-lens objectives



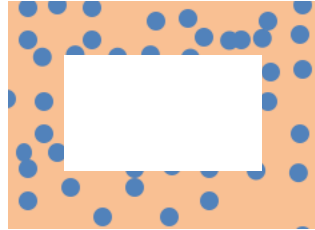
Transparent polymer material



2 Photon Polymerization : glass

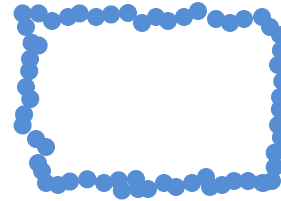
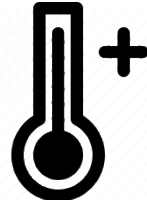


2 Photon Polymerization : glass



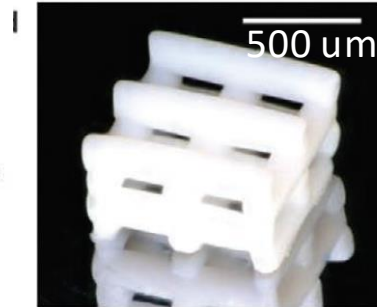
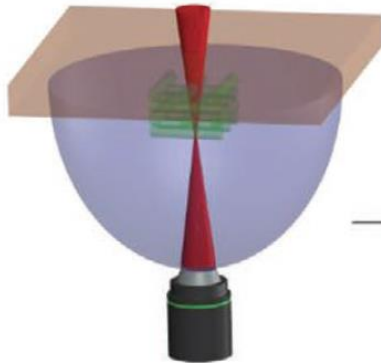
"green body"

oven
→
1300°C



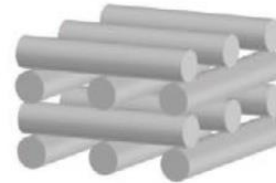
The silica particles sinter and
the polymer are vaporized by the heat
Leaving only the merged silicate particles

a



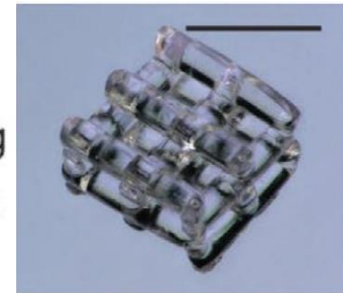
green part

binding
→
100 °C



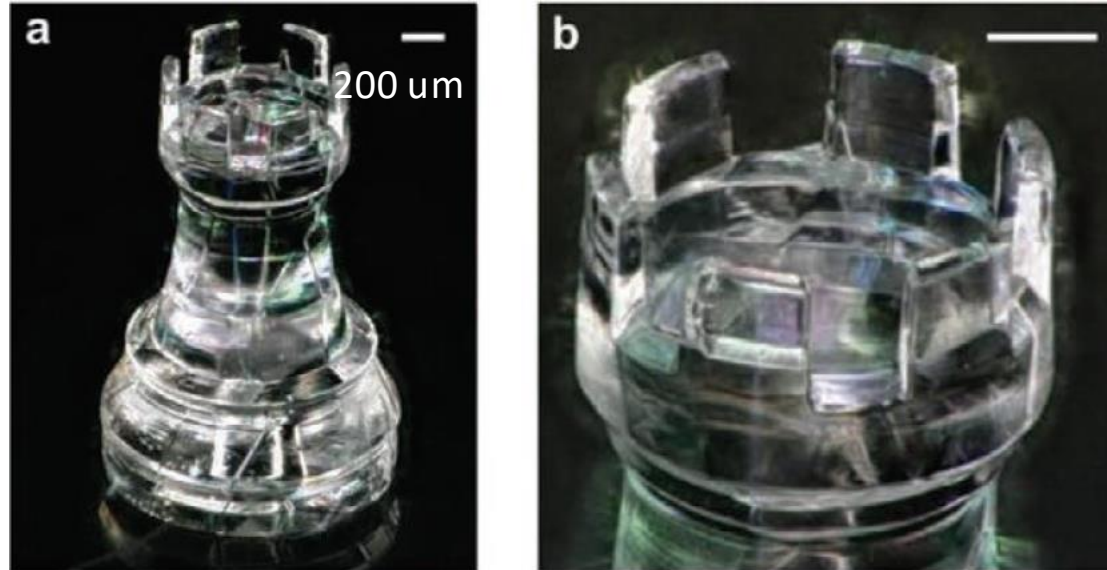
brown part

Sintering
→
1300 °C

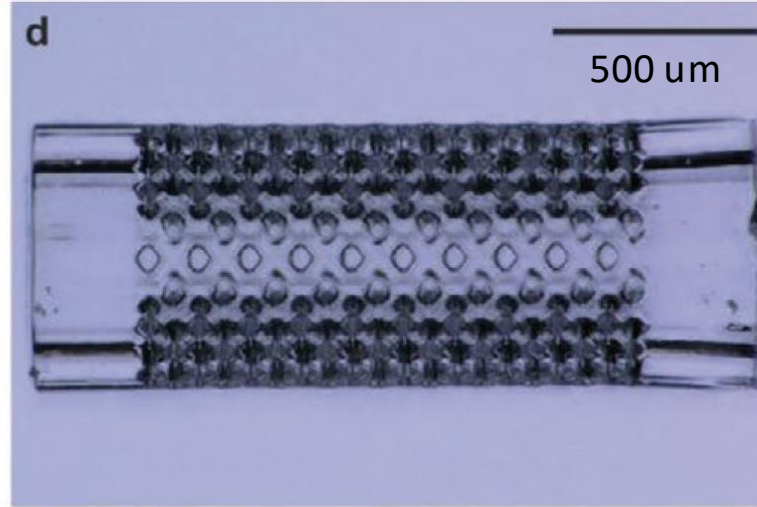


fused silica

Direct laser writing=2 Photon Polymerization

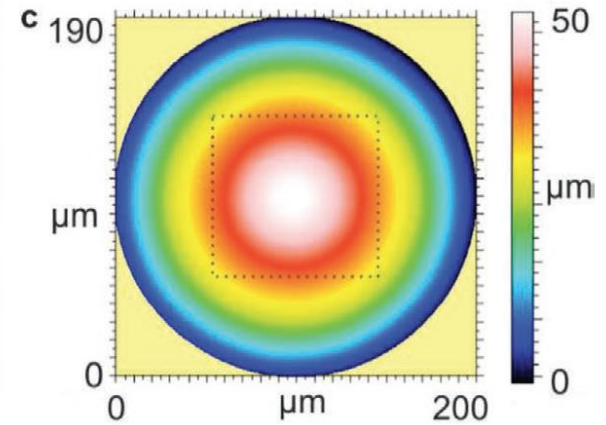
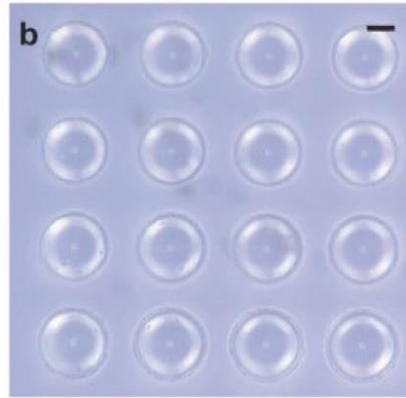
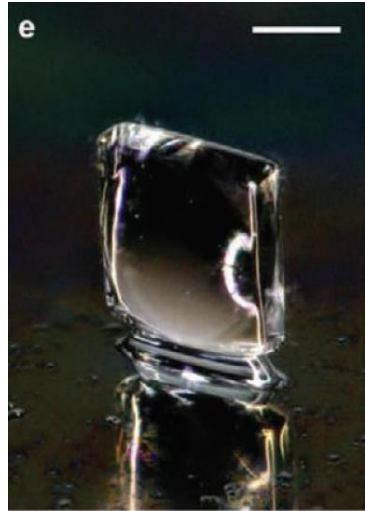


Slicing 5 μm , hatching 1 μm , scan speed 100 mms^{-1}



Micro filter element with 55 μm holes

Slicing 5 μm , hatching 1 μm , scan speed 100 mms^{-1}



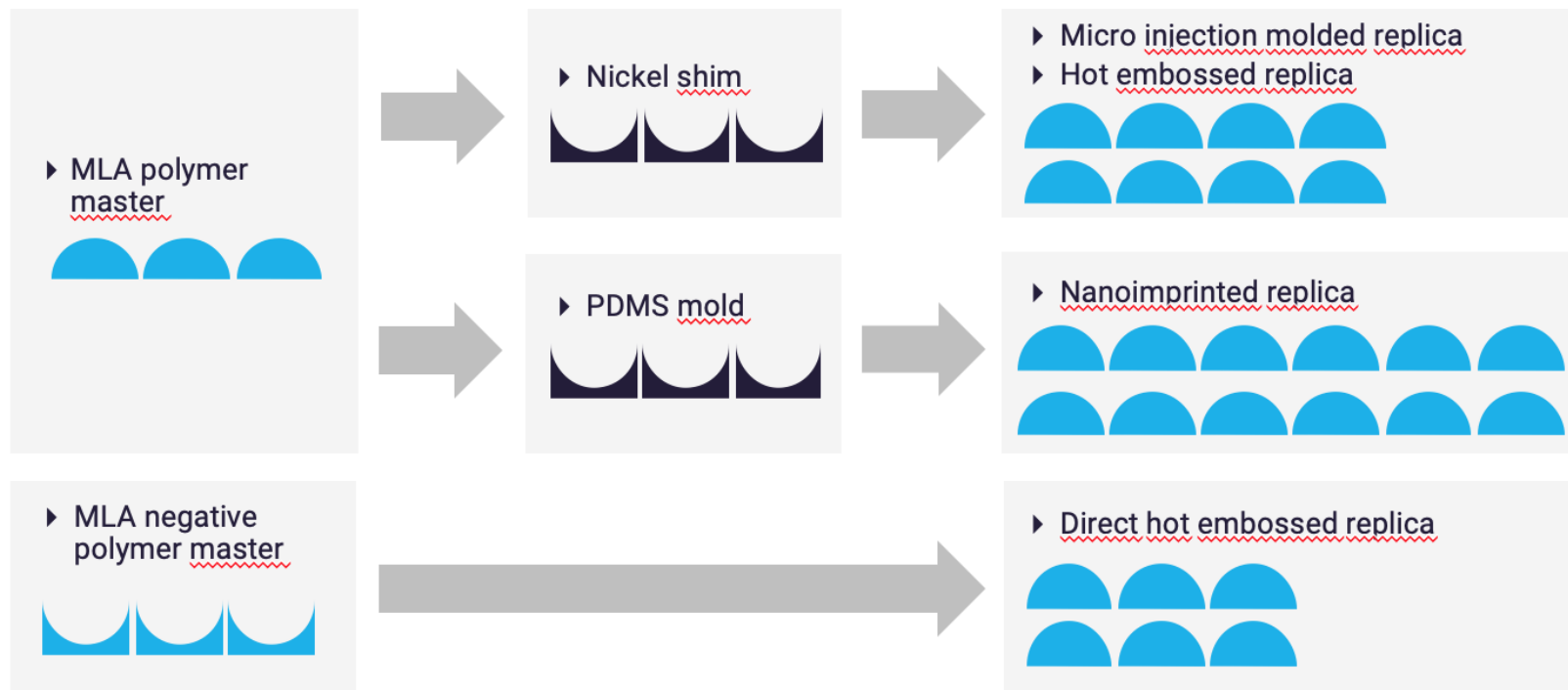
Glass micro lenses

Surface roughness $R_a \approx 6.1 \text{ nm}$



Replication processes

From polymer master to small series production



2-photon
Printer
By Nanoscribe

At Cmi
BM building

